

**Supplementary FIGURES: Mullapudi et al. Low Temperature PE-ALD of tungsten oxide using a novel Tungsten Precursor**

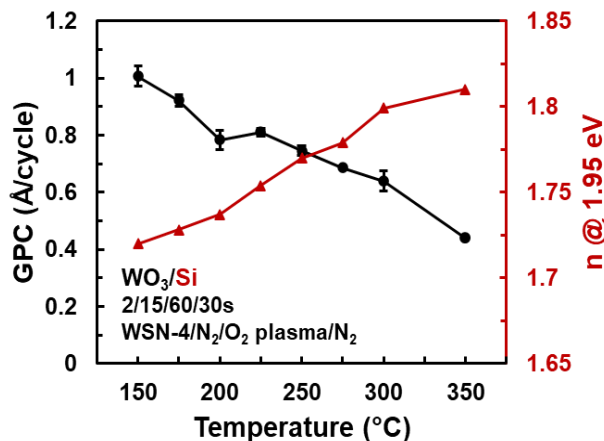


Fig. 1. GPC (black circles) and refractive index (n, red triangles) at 1.95 eV vs. temperature indicated using for 300 cycle ALD WO<sub>x</sub> film.

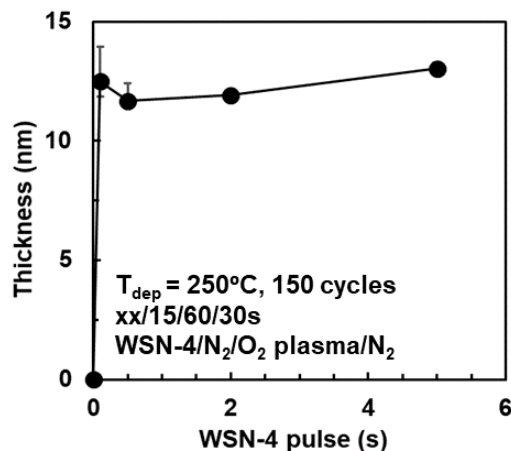


Fig. 2. Thickness vs. WSN-4 pulse time for a 150 cycle WO<sub>x</sub> film deposited at 250°C.

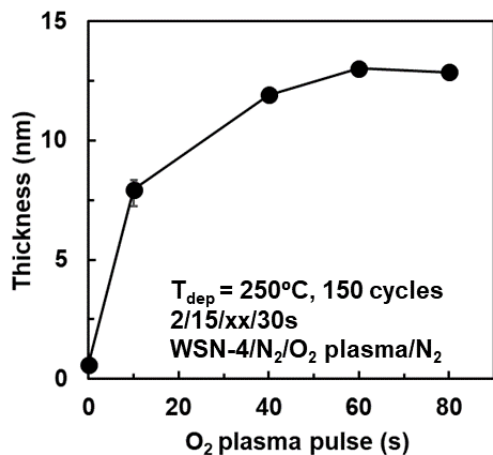


Fig 3. Thickness vs. O<sub>2</sub> plasma pulse time for a 150 cycles WO<sub>x</sub> film deposited at 250°C.

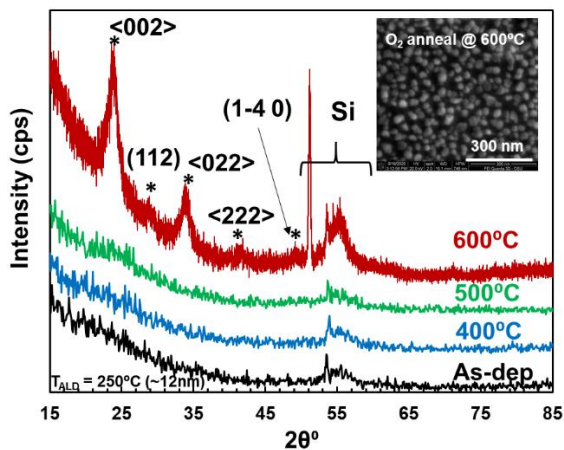


Fig 4. GI-XRD of a 250°C, 150 cycle film isochronally (60 minutes) annealed in O<sub>2</sub> at up to 600°C. Triclinic WO<sub>3</sub> phase seen at 600°C (REF: JCPDS 20-1323). Inset shows a plan SEM image of a 600°C annealed film.